

REMARKS

Applicants filed this divisional application on April 18, 2002. The box instructing the Patent Office to cancel claims 12-52, 56-65, and 71-74 and to renumber the remaining claims as 1-19 was inadvertently left unchecked. In a telephone conversation with Examiner Leanna Roche on April 2, 2002, we discovered this error. This amendment officially cancels claims 12-52, 56-65 and 71-74 and renumbers the remaining claims 1-19. Also claims 12-14 and 18-19 are amended to eliminate method claim dependencies. On September 28, 2002 we also filed a first preliminary amendment adding new claims 20-23.

The Examiner is requested to call the undersigned if any questions arise concerning the above-mentioned application.


Respectfully submitted,

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**VERSION WITH MARKINGS TO SHOW CHANGES MADE
In the Claims**

Claims are canceled 12-52

[53]12. A mesoporous silica film [made by the method of claim 32,
comprising] characterized by:

a disordered porosity, lacking a regular geometric arrangement of pores, and
characterized by an x-ray diffraction peak between about 0.75 and about 2 degrees 2-
theta;

a dielectric constant less than 3.0 that is stable;

a film thickness from about 0.1 μm to about 1.5 μm ; and

an average pore diameter less than or equal to about 20 nm.

[54]13. A mesoporous silica [made by the method of claim 32, comprising]
characterized by:

a disordered porosity as indicated by an absence of an XRD peak in the range from 2
to 6 degrees 2-theta;

a dielectric constant less than 3.0 that is stable;

a film thickness from about 0.1 μm to about 1.5 μm ; and

an average pore diameter less than or equal to about 20 nm.

[55]14. A mesoporous film [made by the method of claim 32, comprising]
characterized by:

a dielectric constant less than 3.0 that is stable;

a film thickness from about 0.1 μm to about 1.5 μm ; and

an average pore diameter less than or equal to about 20 nm.

Claims 56-65 are canceled.

[66]15. A mesoporous film having a dielectric constant less than 2.5, a film thickness from about 0.2 μm to about 1.5 μm , and an average pore diameter less than or equal to about 5 nm.

[67]16. A mesoporous film having a thickness from about 0.2 μm to about 1.5 μm and a standard deviation about said thickness that is less than +/- 5%.

[68]17. A mesoporous silica film prepared from a surfactant containing solution, having a dielectric constant less than 3 that has both a relative stability and an absolute stability in a humid atmosphere, a film thickness from about 0.1 μm to about 1.5 μm , an average pore diameter less than or equal to about 20 nm, and a porosity that is disordered.

[69]18. The mesoporous silica film as recited in claim [68]17, wherein disordered is indicated by the absence of an X-ray diffraction peak in the range of about 2 to about 6 degrees 2-theta.

[70]19. The mesoporous silica film as recited in claim [68]17, wherein disordered porosity is characterized by an X-ray diffraction peak between about 0.75 and about 2 degrees 2-theta.

Claims 71-74 are canceled.